

: Buysemi

CVD SiO₂

(Deposition)		SiH ₄ +O ₂	TEOS	SiCl ₂ H ₂ +N ₂ O	
()	200	450	700	900	1000
	SiO _{1.9} (H)	SiO ₂ (H)	SiO ₂	SiO ₂ (Cl)	SiO ₂
	H			Cl	
(g/cm ³)	2.3	2.1	2.2	2.2	2.2
	1.47	1.44	1.46	1.46	1.46
(10 ⁶ dyne/cm ³)	3C – 2T	3T	1C	3C	3C
(10 ⁶ V/cm)	3-6	8	10	10	10
(mm/min)	40	6	3	3	2.5
(100:1 H ₂ O:HF)	4.9	4.3	4.0	-	3.9

Wafer

.....With Buysemi